

PATENT NUMBER

2

M.H. <sup>D.I.P.E.</sup> SCANNED <sup>AC<sup>3</sup></sup> Q.A.	PATENT DATE
---	-------------

APPLICATION NO. 09/729339	CONT/PRIOR 1 F	CLASS 438	SUBCLASS 29	ART UNIT 28518	EXAMINER Q. HOANG
------------------------------	-------------------	--------------	----------------	-------------------	----------------------

APPLICANTS  
Kyoichi Suwa

TITLE  
Mask, exposure method, line width measuring method, and method for manufacturing semiconductor devices

PTO-2040  
12/99

[illegible]

<input type="checkbox"/> <b>TERMINAL DISCLAIMER</b>	<b>DRAWINGS</b>		<b>CLAIMS ALLOWED</b>	
	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims
<input type="checkbox"/> The term of this patent subsequent to _____ (date) has been disclaimed.	_____ (Assistant Examiner) (Date)		<b>NOTICE OF ALLOWANCE MAILED</b>  _____	
<input type="checkbox"/> The term of this patent shall not extend beyond the expiration date of U.S Patent. No. _____  _____  _____	_____ (Primary Examiner) (Date)		<b>ISSUE FEE</b>  Amount Due _____ Date Paid _____	
<input type="checkbox"/> The terminal _____ months of this patent have been disclaimed.	_____ (Legal Instruments Examiner) (Date)		<b>ISSUE BATCH NUMBER</b>  _____	
<b>WARNING:</b> The information disclosed herein may be restricted. Unauthorized disclosure may be prohibited by the United States Code Title 35, Sections 122, 181 and 368. Possession outside the U.S. Patent & Trademark Office is restricted to authorized employees and contractors only.				

Form PTO-438A  
(Rev. 6/89)

FILED WITH: ☐ DISK (CRF) ☐ FICHE ☐ CD-ROM  
(Attached in pocket on right inside flap)